mr-DWL — Negative Tone Photoresist Series

For direct writing laser @ 405 nm

**Features:**
- Specifically designed for exposure wavelengths above 400 nm
- Direct Writing Laser @ 405 nm, e.g. Diode laser (DWL 66F5)
- High sensitivity
- Excellent thermal and chemical stability of the patterns
- High wet and dry etch stability

**Technical data**

<table>
<thead>
<tr>
<th>Resist</th>
<th>mr-DWL 5</th>
<th>mr-DWL 40</th>
<th>mr-DWL 100</th>
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<tbody>
<tr>
<td>Film thickness µm</td>
<td>3 - 12</td>
<td>20 - 100</td>
<td>20 - 150</td>
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</table>

**Applications:**
- Fast and contactless prototyping by DWL
- Optical applications in micro systems technology
- Etch mask for wet and dry etch processes
- Mould for electroplating
- Mould for stamp fabrication by thermal or UV moulding